



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of

: Confirmation No. 4981

Hiroshi TAKANASHI et al.

: Docket No. 2000-1749

Serial No. 09/739,750

: Group Art Unit 1752

Filed December 20, 2000

: Examiner S. Lee

NEGATIVE-WORKING PHOTOSENSITIVE RESIN
COMPOSITION AND PHOTOSENSITIVE RESIN
PLATE USING THE SAME

THE COMMISSIONER IS AUTHORIZED
TO CHARGE ANY DEFICIENCY IN THE
FEES FOR THIS PAPER TO DEPOSIT
ACCOUNT NO. 23-0975

PETITION FOR EXTENSION OF TIME

Assistant Commissioner for Patents,
Washington, DC 20231

Sir:

Petition hereby is made for a third month extension of time to respond to the communication of June 19, 2002. *Please note that the two month extension of time fee of \$400.00 was paid on November 19, 2002.*

The fee of \$520.00 is

submitted herewith.

to be charged to Deposit Account No. 23-0975. A duplicate copy of this Petition is enclosed.

Small entity status of this application is established by the verified statement under 37 CFR 1.9 and 1.27 which
 is enclosed.
 has been previously submitted.

Respectfully submitted,

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Hiroshi TAKANASHI et al.

By Matthew Jacob

Matthew Jacob

Registration No. 25,154

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December 19, 2002

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